### **Supporting Information**

### Ultrafast Catalyst-Free Growth of Graphene Film on Glass Assisted by Local Fluorine Supply

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Figure S1: Measurement of the gap between the metal fluoride and quartz surfaces.

The cross section of the freely placed quartz on  $BaF_2$  substrate can be observed directly by an optical microscope. The narrow gap between the two surfaces is only ~30 µm, which provides a confined space for the fluorine released from the fluoride at the growth temperature of ~1,000 °C.

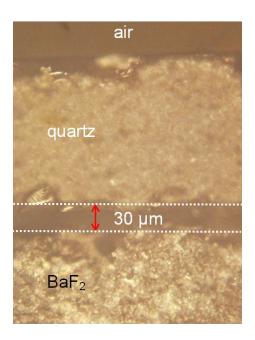
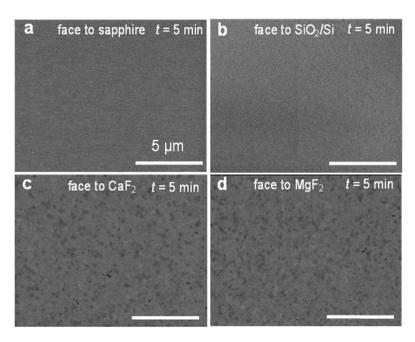


Figure S1. Typical optical image for the cross section of quartz on a BaF<sub>2</sub> substrate.

# Figure S2: Graphene growth on quartz supported by other metal fluorides and non-fluorides

We grew graphene on quartz glass assisted by different fluorides and non-fluorides. Growth supported by  $CaF_2$  and  $MgF_2$  substrates showed the full coverage of graphene film on quartz glass in 5 min. But for the growth supported by sapphire and SiO<sub>2</sub>/Si, no graphene domain is observed on the quartz glass within 5 min.



**Figure S2.** SEM images of graphene grown on the surface of ST-cut quartz glass supported by (a) sapphire, (b) SiO<sub>2</sub>/Si substrate, (c) CaF<sub>2</sub> and (d) MgF<sub>2</sub>.

### Figure S3: Graphene growth on SiO<sub>2</sub>/Si substrate assisted by local-fluorine-supply method

The graphene film on  $SiO_2/Si$  substrate assisted by the local-fluorine-supply method reached full coverage in just 5 min as well (Figure S3a). The 2D/G peak intensity in Raman spectrum (Figure S3b) demonstrates the graphene film mainly consists of monolayers. Our results showed the universality of the local-fluorine-supply method in graphene growth on dielectric substrates.

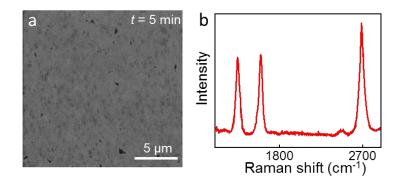


Figure S3. (a) SEM image and (b) Raman spectrum of graphene grown on  $SiO_2/Si$  substrate assisted by fluorine in 5 min.

### Figure S4: High-resolution transmission electron microscopic (HRTEM) images of different graphene samples on quartz glass

A large number of HRTEM images of different graphene quartz glass samples confirmed that the graphene films are primarily monolayers.

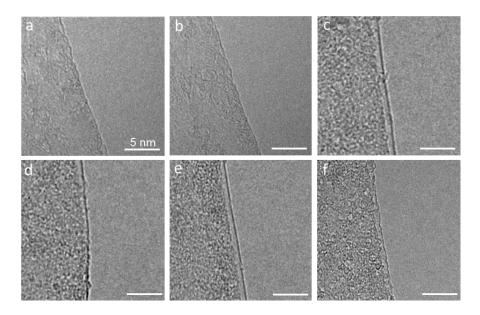


Figure S4. HRTEM images of monolayer graphene film.

## Figure S5: Atomic Force Microscope (AFM) images of graphene films transferred onto SiO<sub>2</sub>/Si substrate.

The thickness of graphene was checked by AFM as shown in Figure S5, which further illustrated that the as-grown graphene films in 5 min are primarily monolayers.

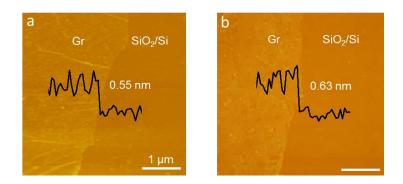
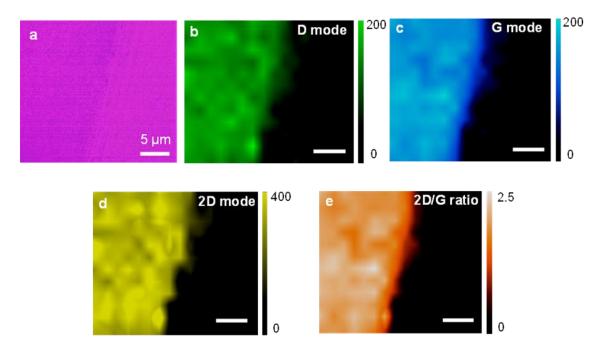


Figure S5. AFM images of the edge of graphene films.

#### Figure S6: Raman mapping of the as-grown graphene film

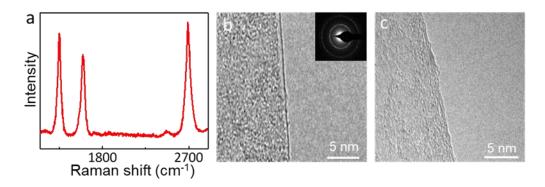
Raman mapping also demonstrates the quality and uniformity of the graphene film which was transferred onto a 300 nm SiO<sub>2</sub>/Si substrate, as shown in Figure S6a (the darker region is the graphene sample). As shown in Figure S6b-e, the slight colour variation in the D, G, 2D mode and  $I_{2D}/I_G$  mapping indicates the uniformity of the graphene film.



**Figure S6.** Raman mapping of graphene film. (a) Optical image of the graphene film. (b-d) The corresponding D, G, and 2D mode mapping. (e)  $I_{2D}/I_G$  ration mapping.

### Figure S7: The quality of graphene films grown without fluorine (grown by quartz confined)

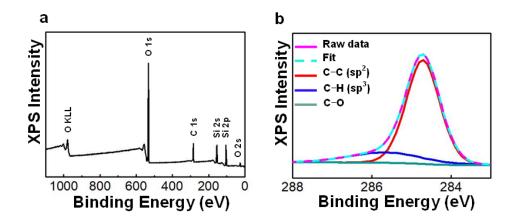
The quality of graphene films grown without fluorine assistance was checked by Raman spectroscopy (Figure S7a), and the graphene films are mainly monolayers demonstrated by 2D/G peak intensity. In addition, HRTEM images illustrated that most of the samples are primarily monolayers with small few-layer regions (Figure S7b-c), and the selected area electron diffraction (SAED) showed the polycrystalline structure of graphene film grown without fluorine assistance (Figure S7b). These characteristics are all corresponding with that of graphene grown by the local-fluorine-supply method.



**Figure S7.** Quality of graphene film grown without fluorine (grown by quartz confined). (a) A representative Raman spectrum of graphene film. (b-c) HRTEM images of (b) monolayer and (c) multilayer regions. The inset is the corresponding SAED.

#### Figure S8: X-ray photoelectron spectroscopy (XPS) of graphene on quartz glass

We find the absence of F 1s peak in the survey of the XPS spectrum as shown in Figure S8a. In addition, according to the C 1s peak analysis, there are no C-F bonds formed in the as-grown graphene film. Therefore, we can conclude that there is no fluorine doping in the graphene films.



**Figure S8.** (a) Representative survey XPS spectrum of the fluorine assisted graphene glass. (b) C 1s XPS spectrum displayed the absence of C-F bonds, indicating the high quality of graphene glass without fluorine doping.

### Figure S9: Comparison of utilization efficiency of CH<sub>4</sub> with fluorine and without fluorine by Mass Spectroscopy (MS)

The measurements of mass spectroscopy were employed to analyze the exhaust of the CVD system. The results of MS (Figure S9) indicated that utilization efficiency of  $CH_4$  with fluorine assisted is about 15% higher than that of without fluorine. However, the concentration of F and  $CH_3F$  in the CVD system is too small to be detected by MS.

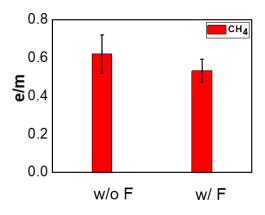
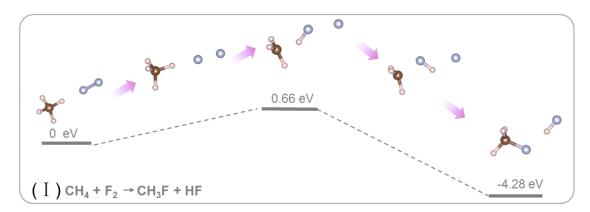


Figure S9. Comparison of utilization efficiency of CH<sub>4</sub> by using mass spectroscopy.

#### Figure S10: The energy profile of CH<sub>3</sub>F formation

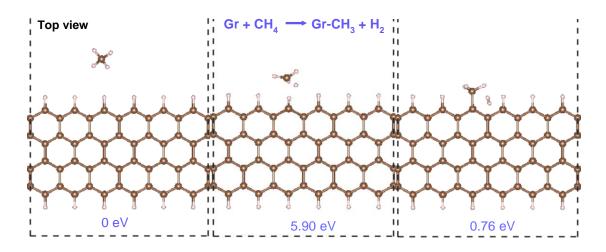
For the formation of  $CH_3F$ , the reaction barrier is only 0.66 eV and the reaction is highly exothermic, therefore, we can expect a considerable amount of  $CH_4$  molecules was converted into  $CH_3F$  molecules in the narrow gap, as shown in Figure S10.



**Figure S10.** The formation of  $CH_3F$  in gas phase and the corresponding energy profile.

#### Figure S11: The first step for CH<sub>3</sub>F reacting with graphene edge

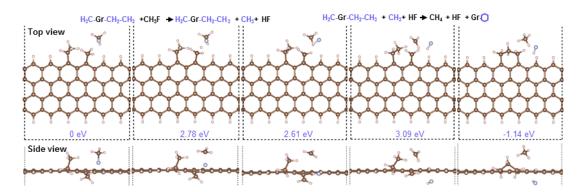
The attachment of carbon atoms to graphene edge by the collision of gas phase molecules with the graphene edge is a necessary step for the graphene growth. We firstly assume that feedstock methane could be carbon precursor candidate to decompose and directly involved into the graphene edge growth, the entire process is shown in Figure S11. From left to right in this figure successively are initial, transition and final states.



**Figure S11.** The calculation model of first step for CH<sub>4</sub> attaching to graphene edge. From left to right in this figure successively are initial, transition and final states.

#### Figure S12: The third step for CH<sub>3</sub>F reacting with graphene edge

For  $CH_3F$  incorporation at the growth edge, the last route is a two-step reaction with two hydrogen atoms separately scratched, as shown in Figure S12. And the according relative energy is shown below the calculation model.



**Figure S12.** The concrete reaction process of third step for  $CH_3F$  attaching to graphene edge, composed of two steps. The according relative energy is shown in the calculation model.

Table S1 Reported growth time to realize a full-coverage graphene film on   insulating substrates.	
Group	Growth time (min)
Yuegang Zhang <sup>[1]</sup>	420
Xiaoming Xie <sup>[2]</sup>	360
Yunqi Liu <sup>[3]</sup>	240
Zhongfan Liu <sup>[4]</sup>	180
Hee Cheul Choi <sup>[5]</sup>	120
Zhongfan Liu <sup>[6]</sup>	75
This work	5

Supporting Table 1. Reported growth time to realize a full-coverage graphene film on insulating substrates.

#### Supporting Method: Density functional theory calculation.

All the calculations above were performed with the Vienna *ab*-initio Simulation Package <sup>[7,8]</sup> with density functional theory using the method of the project augmented wave<sup>[9]</sup>. The exchange and correlation potentials were treated by the Perdrew-Burke-Ernzerhof (PBE) functional within the generalized gradient approximation (GGA)<sup>[10]</sup>. 400 eV was taken as energy cutoff, and we fully relaxed all the structures considering to let both the energy and force converge to  $10^{-4}$  eV and 0.02 eV/ Å, respectively. The unit cell of slab models is 14.75 Å × 30.00 Å for the zigzag graphene nanoribbons. To avoid interaction between the adjacent unit cell, a vacuum layer along the z direction was kept as large as 14 Å. Unless specified, spin-polarization was used in all the calculations to fully include the effects of edge and small molecules. The energy barrier of each reaction step was studied by using the climbing image nudged elastic band (CI-NEB) approach <sup>[11]</sup>.

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